



Item	Minimum Capability	Maximum Capability	Tolerance	Remarks
Metal Finishing: Hal Lead Free (SnCuNi) Chemical Tin (Inm.Sn) (*) Chemical Silver (Inm.Ag) Electroless Ni Inmersion Gold (ENIG)	Ni: 3 μm Au: 0,04 μm	Ni: 7 μm Au: 0,07 μm	-	Sn100C Alloyage (*) Subcontracted
Final Finishing: Liquid PhotoImageable Solder Mask Ink Legend Conductive Carbon Ink Peelable Mask	-	-	-	A wide range of colours A wide range of colours
Raw Material: FR-4 Tg Standard FR-4 High Tg	130 ºC 150 ºC	140ºC 180 ºC	-	Depending on the manufacturer
Base Copper	17 μm	70 μm	-	Under request (consult delivery time): 105 μm
Plated Through Hole (PTH)	200 μm	-	+ 0,10 / - 0,05 mm	Or equivalent tolerance
Non Plated Through Hole (NPTH)	300 μm	-	+ 0,10 / -0 mm	Or equivalent tolerance
Width and isolation of copper conductors (Base Copper)	100 μm (17 μm) 125 μm (35 μm)	-	± 25% ± 30%	-
	125 μm (35 μm) 200 μm (70 μm)	-	± 30% ± 30%	





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Copper annular ring (Base Copper)	100 μm (17 μm)		-	
	125 μm (35 μm)	-		Recommendation: for a good soldering surface, for component holes \geq 200 μm
	250 μm (70 μm)			
Distance between NPTH and copper conductor	200 μm	-	-	-
Distance between copper conductor and board edge (routed)	150 μm	-	-	-
Misalignement between copper and PTH	,	-	± 100 μm	-
Misalignement between outline and PTH	+	-	± 150 μm	
Distance between a copper conductor and theorical scoring axis	500 μm	-	-	-





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Maximum hole to be plugged with peelable mask	0,30 mm	1,80 mm	-	-
Distance between peelable mask and copper pad	0,80 mm	-	-	-
Solder Mask annular ring	50 μm	-	-	-
Solder Mask bridge	100 μm	-	-	-
Distance between solder mask clearance and copper conductor	50 μm	-	-	-
Misalignement between solder mask and copper	-	-	± 150 μm	-





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Ink Legend width	R23	100 μm	-	-	-
Misalignement between ink legend and copper		-	-	± 200 μm	-
Carbon ink width		600 μm	-	-	-
Separation between carbon conductors		400 μm	-	-	-
Platted Wall thickness		20 μm	60 μm	-	Average: 25 μm
Scoring positioning (taken on axis)		-	-	± 150 μm	-





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Core thickness after scoring process	200 µm		± 150 μm	Standard: 300 μm
Misalignement between top-bottom scoring blades		-	± 150 μm	-
Final Thickness	0,50 mm	3,2 mm	± 10 % (e > 1,0 mm) ± 100 μm (e ≤ 1,0 mm)	-
DUW & I WIST esquinas en cont	s A, B y C en contacto con	0,75% of diagonal	-	-
Final pcb dimensions (routing)	15 x 15 mr	n 600 x 500 mm	< 30 mm: ± 0.10 mm < 120 mm: ± 0.15 mm >120 mm: ± 0.20 mm	-
Other	-	-	-	According to IPC-A-600 revision G Standard

REMARKS

1.- The extra Cu deposition is performed by an electrolytic process; therefore It is extremely convenient that the density of Cu on both sides is similar. This reduces the irregularities in total Cu thickness, warping and bending, reduction in PTH diameters and the excess of Cu on conductors.